Application No.: 10/722,815 Docket No.: 30205/39509

REMARKS

This paper is filed in response to the Office Action mailed on July 27, 2004.

In the Office Action, claim 4 is indicated as being allowable and therefore claims 1 and 4 have been combined thereby rendering amended claim 1 and dependent claims 2 and 3 allowable.

With respect to new claims 5-9, Applicants respectfully submit that U.S. Patent No. 6,087,222 ("Lin") does not teach or suggest the process of claim 5. The method of claim 5 requires a spike annealing to be carried out in an ammonia, hydrogen or nitrogen atmosphere. Lin does not suggest a spike annealing step but, instead, suggests only "annealing" in column 3. Specifically, Lin states: "After annealing the concentration of the boron dopant in the sidewalls of the substrate 11 was from about 8E16 atoms/cm³ to about 8E17 atoms/cm³." Thus, Lin does not teach or suggest spike annealing or spike annealing in an ammonia, hydrogen or nitrogen atmosphere. Lin teaches nothing about the atmosphere for any annealing process, and nothing about spike annealing.

Therefore, Lin cannot serve as an anticipating reference or an obviating reference for new claim 5 or dependent claims 6-9. Accordingly, an early action indicating the allowability of new claims 5-9 is earnestly solicited.

Applicants respectfully submit that all claims are allowable and that this application be passed to allowance.

The Commissioner is authorized to charge any fee deficiency required by this paper, or credit any overpayment, to Deposit Account No. 13-2855.

Dated: October 27, 2004

Respectfully submitted,

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